

ELECTRONICS

## Solvents in Solvents in Electronics - Resist Stripping

## Why is the role of solvents essential?

Microchips power everything from smartphones to cars, and making them requires absolute precision. A key step in their production is cleaning the wafer, the thin slice of silicon where circuits are built. To ensure that no tiny residues interfere with performance, solvents are used to gently and effectively clean the surface, making sure the final chips work reliably and at the highest quality.

In semiconductor manufacturing, solvents are essential to maintain the precision and quality demanded by modern electronics. After processing the film on a wafer, where microstructures are formed through exposure and etching, photoresist residues remain. If not removed, these residues can compromise the wafer's electrical properties and, ultimately, the performance of the semiconductor device.

Solvents are indispensable in this cleaning process: their unique chemical properties allow them to dissolve and eliminate photoresist without harming the underlying materials. This ensures both the cleanliness of the wafer and the integrity of delicate microstructures, enabling the production of high-performance microchips that meet the industry's strict standards.

Beyond precision, solvents also contribute to efficiency and sustainability in semiconductor manufacturing, improving product quality and yields while supporting advanced and resource-optimised production practices.

INDUSTRIAL USE

## SPOT ON

2,5,7,10-tetraoxaundecane (TOU) (CAS 4431-83-8 - EC 224-631-8)

2-(2-Aminoethoxy)ethanol (CAS: 929-06-6 - EC: 213-195-4) n-Butyl acetate (CAS: 123-86-4 - EC: 204-658-1)

2-butoxyethanol, ethylene glycol monobutyl ether (EGBE) (CAS: 111-76-2 - EC: 203-905-0)

Butyl Diglycol, Diethylene glycol monobutyl ether (DGME)
(CAS 112-34-5 – EC: 203-961-6)

N,N-Dimethylacetamide (DMAC) (CAS: 127-19-5 - EC: 204-826-4)

Isopropanolamine (CAS: 78-96-6 - EC: 201-162-7)
Methoxypropylacetate, propylene glycol methyl ether acetate (PGMEA) (CAS:108-65-6 - EC: 203-603-9)

B-methylpyrrolidone, 1-Methyl-2-pyrrolidone (NMP) (CAS: 872-50-4 - EC: 212-828-1)

Methanesulfonic acid, methylsulfonic acid (MSA) (CAS: 75-75-2 - EC: 200-898-6)



## **Benefit Green Deal**

Globally competitive and resilient industry - Cleaner energy and cutting-edge clean technological innovation

